

# **CLEAN EQUIPMENT FOR REMOVING POLYMER RESIDUES ON SIDEWALLS OF METAL LINES AND METHOD THEREOF**

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## **ABSTRACT OF THE INVENTION**

10 A clean equipment for removing polymer residues on sidewalls of  
metal lines and method thereof are provided. The present clean  
equipment comprises a stripping solution bath, at least an organic  
solvent bath, an overflow bath and a dryer. A gas bubbler and a lattice-  
like cassette stage are positioned within the organic solvent bath. The  
gas bubbler provides gas flow in the organic solvent bath to increase the  
convection of the organic solvent. The lattice-like cassette stage is used  
for supporting cassettes for carrying wafers. By way of increasing the  
15 number of bubbling apertures of the gas bubbler and designing the gas  
bubbler structure in a way that preventing the bubbling apertures from  
being blocked by the lattice-like cassette stage, the convection  
effectiveness of the organic solvent is increased. Thereby, the stripping  
solution can be effectively removed with the organic solvent. Besides,  
20 lengthening the drip dry time of the wafer over each bath so as to  
eliminate the quantity of the stripping solution left on the wafer drawn in  
the overflow bath. By the above measures, metal corrosion occurred on  
the sidewalls of the metal lines formed on the wafer is significantly  
reduced.